

*Amendments to the Claims*

This listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Currently Amended) A system for photoresist recovery comprising:
  - a nozzle to dispense a photoresist;
  - a bowl having an interior region and an interior surface;
  - a wafer platform disposed within the interior region of the bowl;
  - a wafer spindle, coupled to the wafer platform, ~~the wafer spindle constructed and arranged~~ to spin the wafer platform to propel an excess amount of photoresist deposited upon a wafer placed upon the wafer platform to the interior surface of the bowl;
    - at least one a photoresist recovery container coupled to the bowl via a recovery drainpipe;
    - a recovery drainpipe block capable of being positioned in front of the recovery drainpipe to prevent contaminants from entering the recovery drainpipe;
    - a perimeter drain formed within the bowl by extending around the perimeter of the bowl such that the excess amount of photoresist propelled from the wafer proceeds through the perimeter drain to the photoresist recovery container;
    - wherein the perimeter drain comprises:
      - a ~~concave~~ concave conduit for reducing the surface area contacting the photoresist being recovered; and
      - a weeping seal to permit a wash solvent to wash the excess amount of photoresist propelled from the wafer through the perimeter drain to the ~~photoresist~~ photoresist recovery container.

2-3. (Cancelled)

4. (Currently Amended) The system of claim 1, wherein the perimeter drain is formed level with a wafer rotation position within the interior surface of the bowl.

5. (Currently Amended) The system of claim 1, wherein a solvent-rich environment is maintained within the recovery drainpipe.

6-7. (Cancelled)

8. (Previously Presented) The system of claim 30, further comprising:  
one or more additional perimeter drains formed within the bowl to recover one or more additional types of photoresists in corresponding photoresist recovery containers.

9-27. (Cancelled)

28. (Previously Presented) The system of claim 1, wherein the wash solvent is the same as or compatible with the solvent used in the photoresist being recovered.

29. (Previously Presented) The system of claim 1, wherein the perimeter drain is angled so as to facilitate the movement of photoresist to a recovery drain.

30. (Currently Amended) The system of claim 1, further comprising a waste drain formed ~~within~~ to communicate with the bowl.

31. (Previously Presented) The system of claim 1, further comprising a filtering apparatus to remove particles from the recovered photoresist.

32. (Previously Presented) The system of claim 1, further comprising a treating apparatus to treat the recovered resist to permit its reuse.

33. (Currently Amended) The system of claim 32, wherein the treating apparatus ~~further~~ comprises a viscosity monitoring apparatus used to control the addition or evaporation of solvent, to or from the recovered photoresist.

34. (Currently Amended) The system of claim 1, wherein the concave conduit ~~comprises~~ has an approximately semicircular toroid shape.

35. (Currently Amended) A system for photoresist recovery comprising:  
a nozzle to dispense a photoresist;  
a bowl having an interior region and an interior surface;  
a wafer platform disposed within the interior region of the bowl;  
[see change to claim 1] a wafer spindle coupled to the wafer platform, ~~the wafer spindle constructed and arranged~~ to spin the wafer platform to propel an excess amount of photoresist deposited upon a wafer placed upon the wafer platform to the interior surface of the bowl;  
at least one a photoresist recovery container coupled to the bowl via a recovery drainpipe;

a recovery drainpipe block capable of being positioned in front of the recovery drainpipe to prevent contaminants from entering the recovery drainpipe;

a perimeter drain formed within the bowl by extending around the perimeter of the bowl such that the excess amount of photoresist propelled from the wafer proceeds through the perimeter drain to the photoresist recovery container;

wherein the perimeter drain comprises a ~~eoneaved~~ concave conduit for reducing the surface area contacting the photoresist being recovered;

a waste drain formed within the bowl;

one or more additional perimeter drains formed within the bowl to enable the separate recovery of one or more additional types of photoresists, which enables the system to change photoresist types while in production, thus reducing down time for photoresist changing operations; and

a weeping seal to permit a wash solvent to wash the excess amount of photoresist propelled from the wafer through one of the perimeter drains to ~~the~~ a corresponding ~~photoresisit~~ photoresist recovery container.

36. (Currently Amended) The system of claim 35, wherein the spindle is adjustable to alternate spindle heights to accommodate the one or more of the additional perimeter drains.

37. (Previously Presented) The system of claim 35, wherein the position of the bowl is adjustable relative to the wafer platform.

38. (Cancelled)